



Effect of the two-dimensional strain on the equilibrium crystal shape of GaAs by ab-initio thermodynamics

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- **Introduction**

- Integration of GaAs on Si CMOS platform
- Purpose

- **Homo-epitaxy of GaAs on GaAs(001)**

- Unstrained crystal shape simulation of GaAs
- DFT + Statistical thermodynamics

- **Hetero-epitaxy of GaAs on Si(001)**

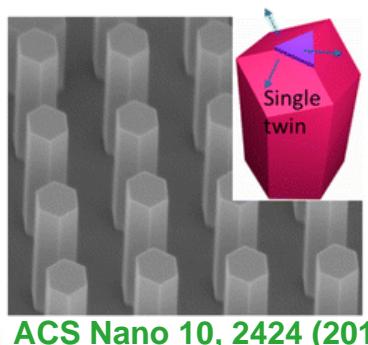
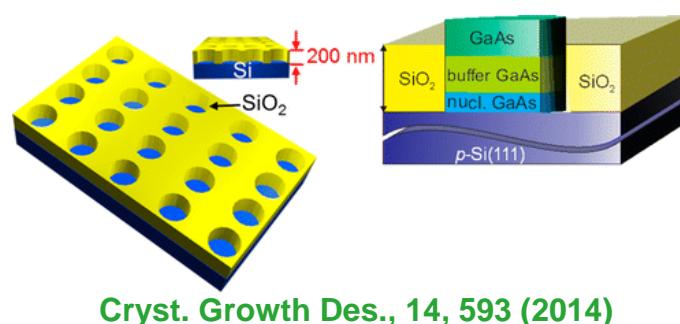
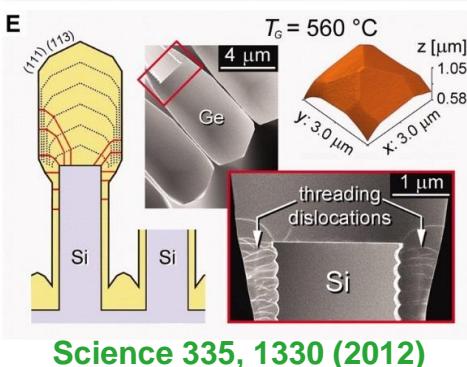
- Strained crystal shape simulation of GaAs
- DFT + FEM + Statistical thermodynamics

Integration of III-V on Si CMOS platform

	e ⁻ mobility (cm ² /Vsec)	h ⁺ mobility (cm ² /Vsec)	Lattice constant (Å)
Si	1,400	500	5.43
Ge	3,900	1,900	5.65
GaAs	8,000	400	5.65
InAs	33,000	460	6.06

Difficulties

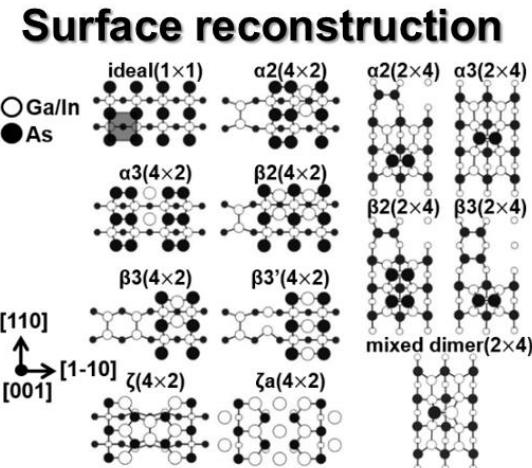
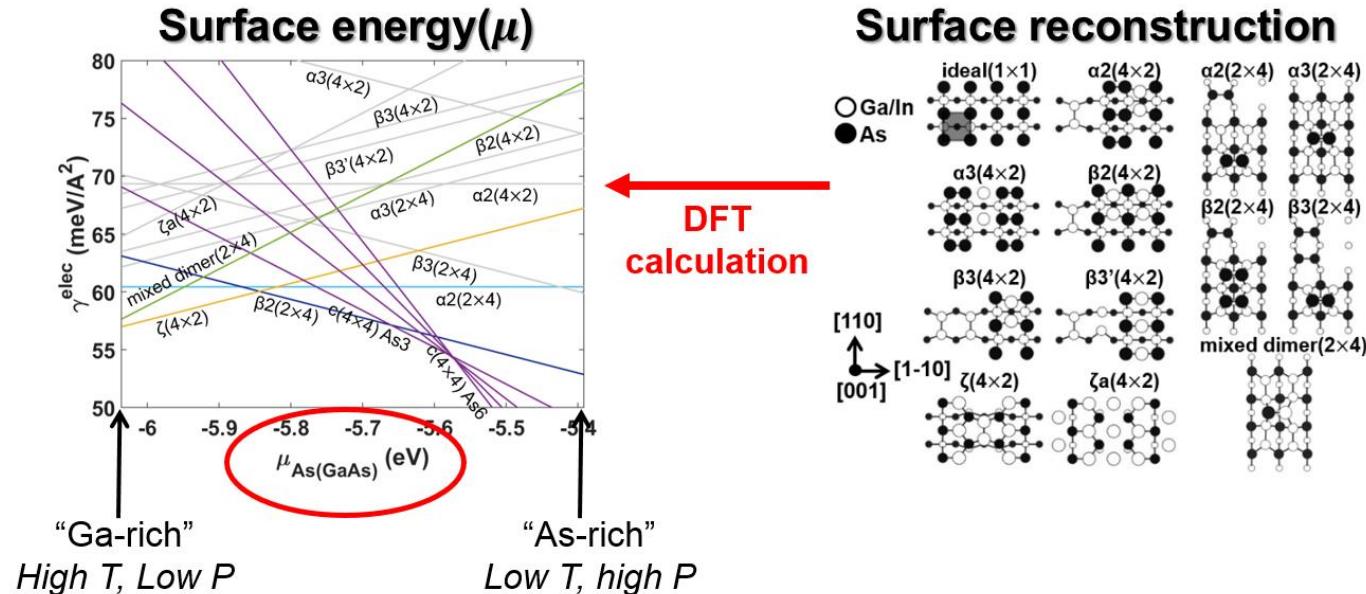
- Large lattice mismatch → dislocation
- Different thermal expansion coefficients → crack
- Polar material on a nonpolar substrate → antiphase domain



Selective Area Growth

- Dislocation → Confined to the bottom
- Crack → inhibition of propagation
- Antiphase domain → Reduction due to small number of nuclei

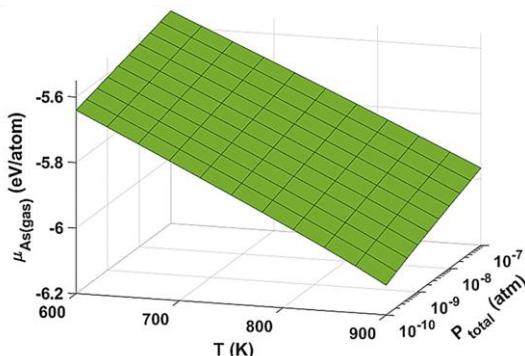
ab-initio thermodynamics



x-axis: $\mu_{\text{As(GaAs)}} = \mu_{\text{As}(g)}(T, P) !!$

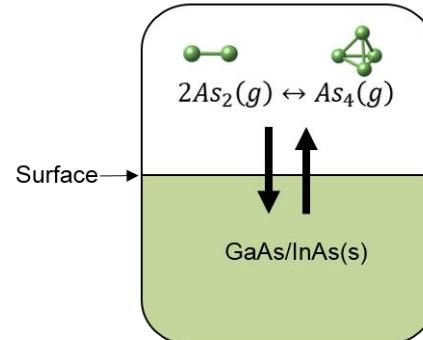
DFT calculation

$$\mu_{i(g)}(T, P) = \mu_{i(\text{gas})}^o(T, P^o) + k_B T \ln \frac{P_{i(\text{gas})}}{P^o}$$



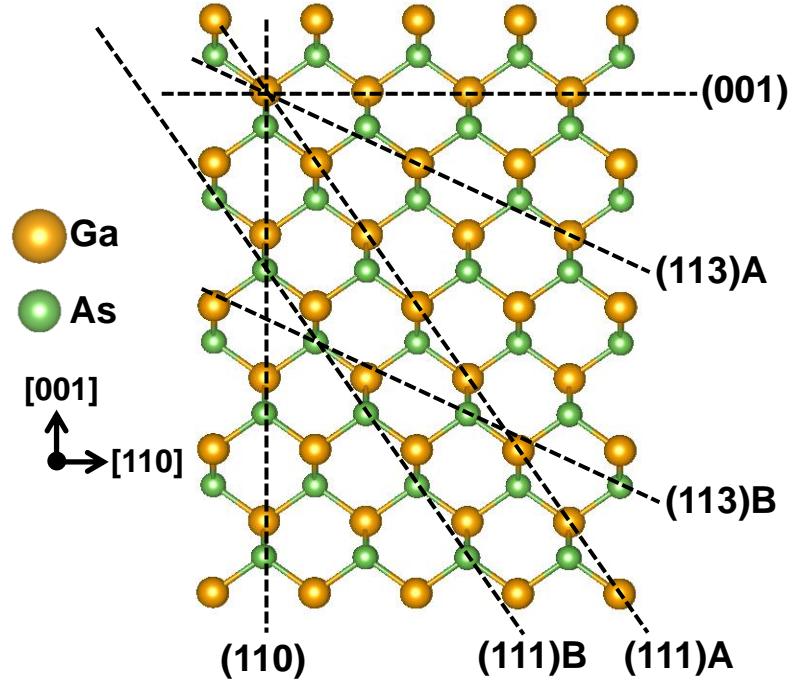
Equilibrium

$$\mu_{\text{As}(g)} = \mu_{\text{As(GaAs)}}$$



Unstrained shape: Wulff shape

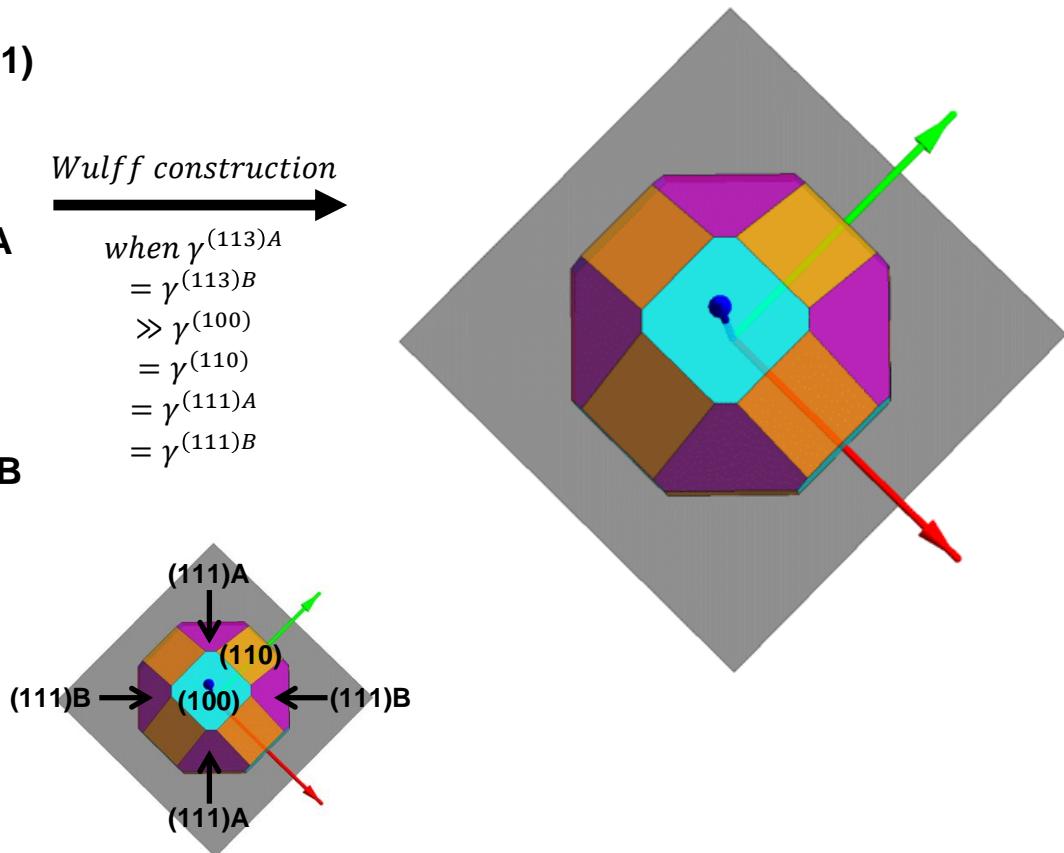
GaAs crystal(ZB)



Wulff construction

$$\begin{aligned} &\text{when } \gamma^{(113)A} \\ &= \gamma^{(113)B} \\ &\gg \gamma^{(100)} \\ &= \gamma^{(110)} \\ &= \gamma^{(111)A} \\ &= \gamma^{(111)B} \end{aligned}$$

Wulff shape



Wulff construction: $d^{(hkl)} \propto \gamma^{(hkl)}$

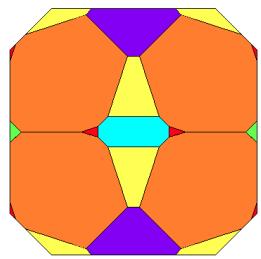
Wulff shape vs. homo-epitaxial shape

[110]
[001]
[1-10]

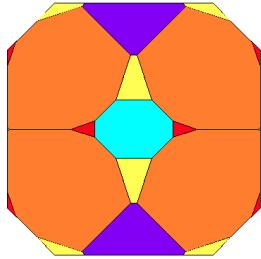
Top View

- (100)
- (110)
- (111)A
- (111)B
- (113)A
- (113)B

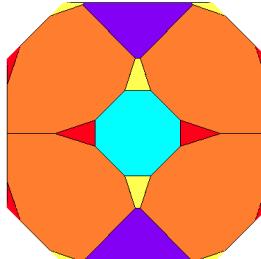
Simulation



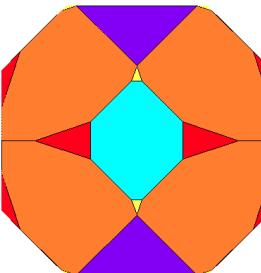
T: 973 K,
 P_{As} : 10^{-3} atm



T: 973 K,
 P_{As} : 10^{-5} atm

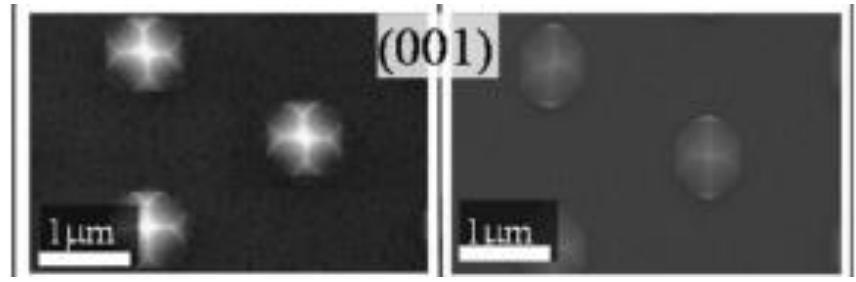


T: 973 K,
 P_{As} : 10^{-7} atm

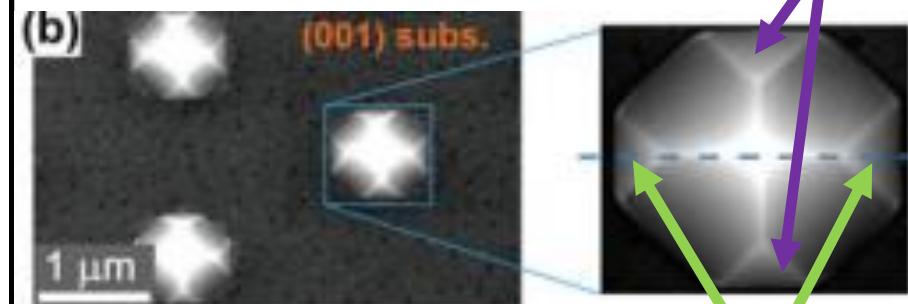


T: 973 K,
 P_{As} : 10^{-9} atm

Experiments



T: 1023 K T: 873 K
[TMGa]: 2.7×10^{-6} atm [TMGa]: 2.7×10^{-6} atm
[AsH₃]: 5.0×10^{-4} atm [AsH₃]: 1.0×10^{-3} atm

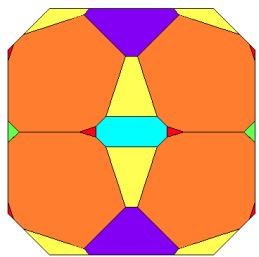


(001) subs.

T: 973 K

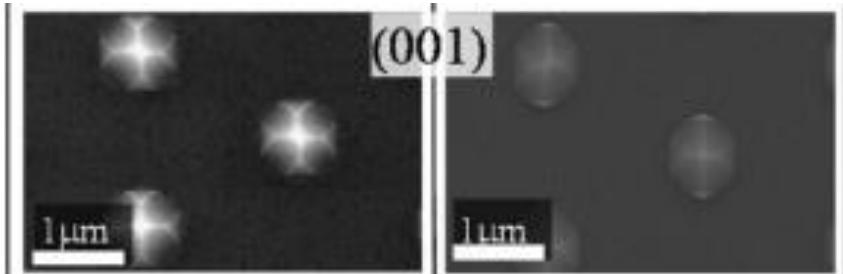
Wulff shape vs. homo-epitaxial shape

Simulation



T: 973 K,
 $P_{As}: 10^{-3}$ atm

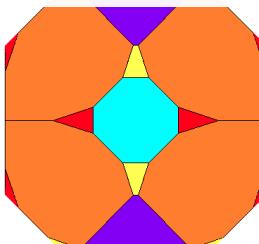
Experiments



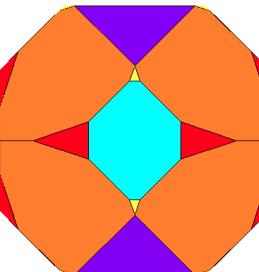
Experimentally found (111)B facet X

1. Experimental crystal shape is determined by kinetics
2. There is some unknown (111)B reconstructions

- (100)
- (110)
- (111)A
- (111)B
- (113)A
- (113)B



T: 973 K,
 $P_{As}: 10^{-7}$ atm



T: 973 K,
 $P_{As}: 10^{-9}$ atm



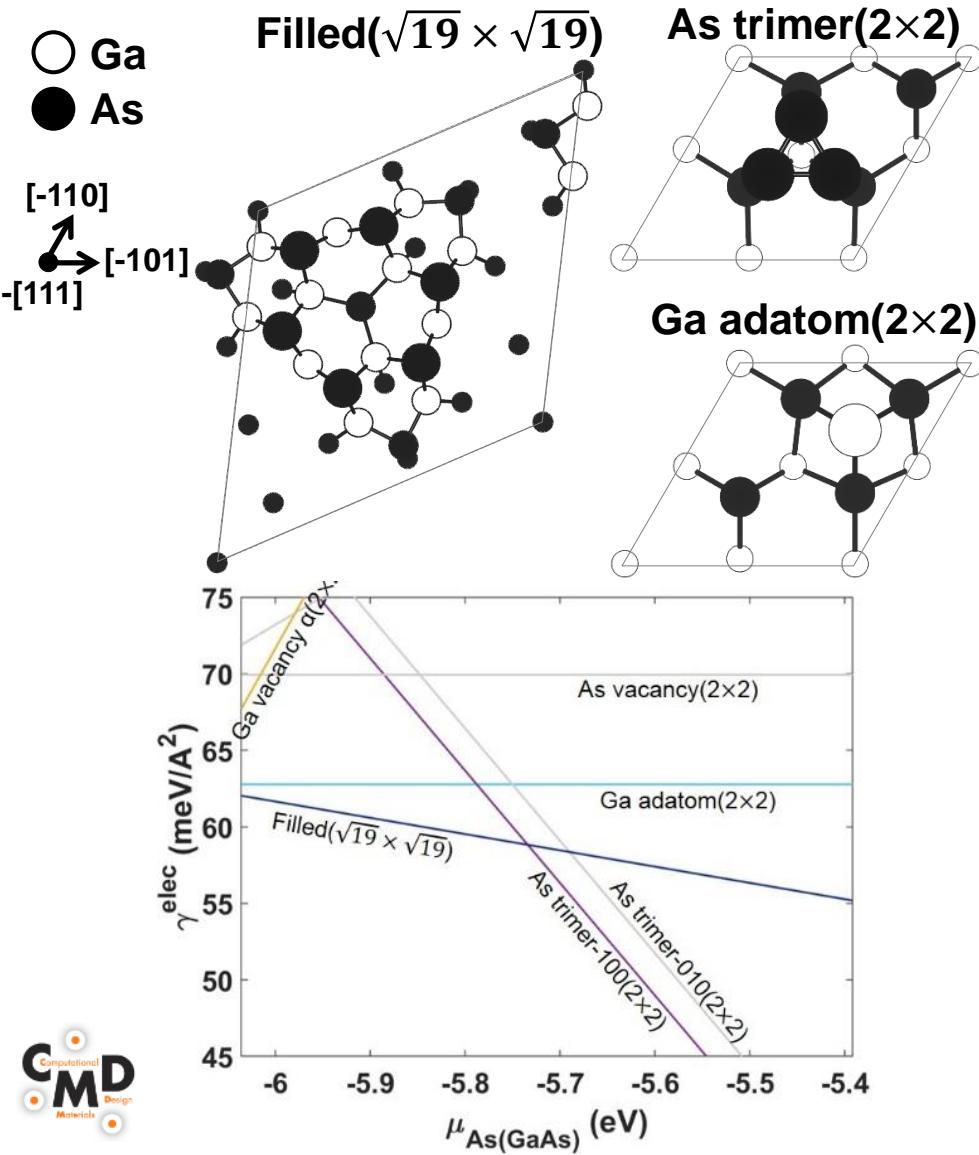
TMGa & TBAs or AsH₃

T: 973 K

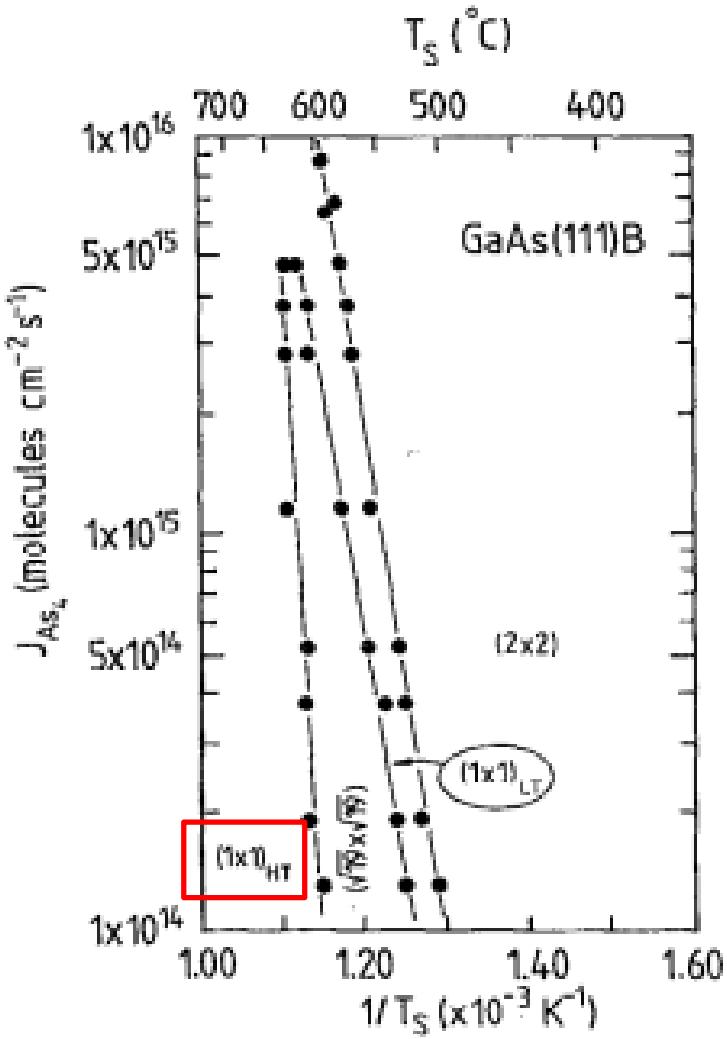
J. Cryst. Growth, 298, 616 (2007)
J. Mater. Res., 26, 2127 (2011)

(111)B: other reconstructions?

Simulation



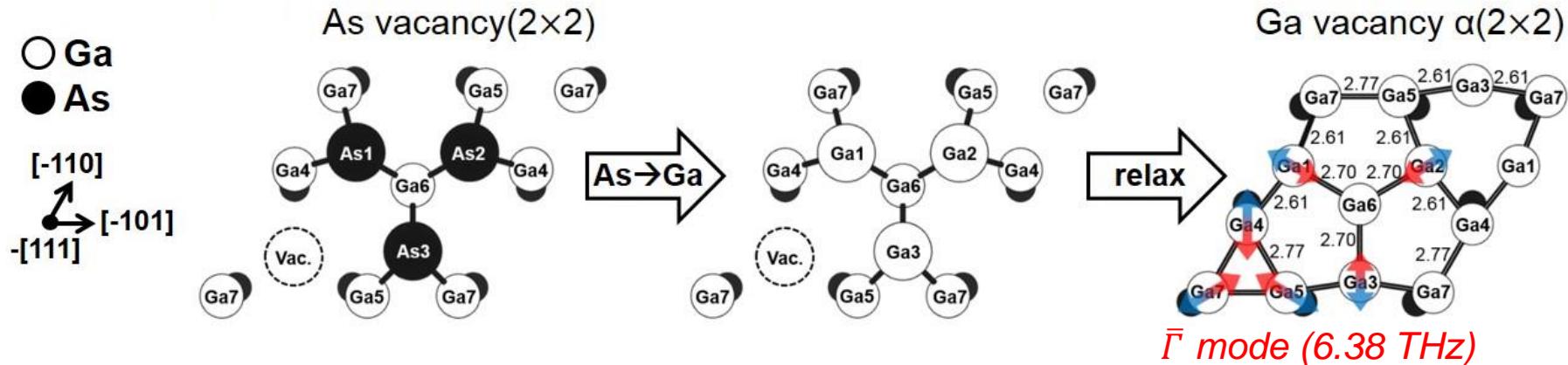
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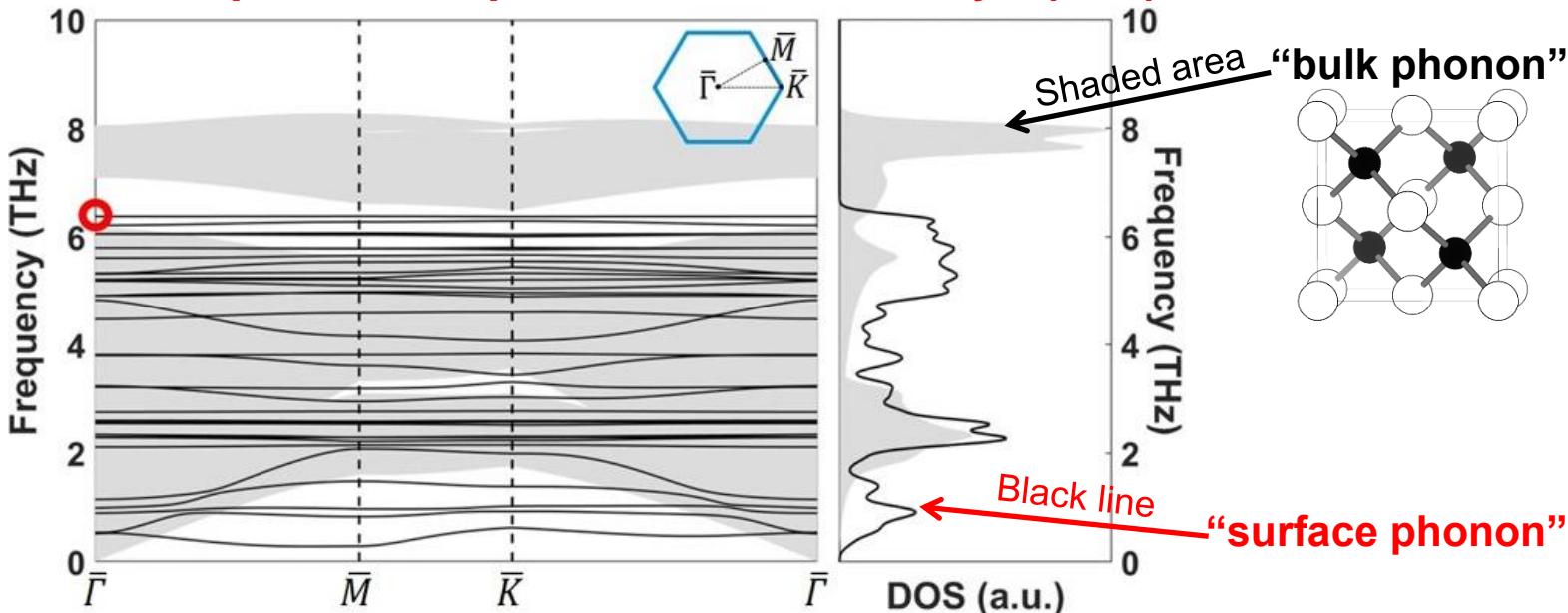
Appl. Phys. Lett., 62, 1370 (1993)

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New GaAs(111)B reconstruction

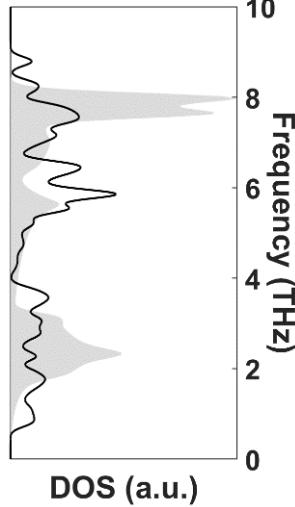


Surface phonon dispersion of Ga vacancy $\alpha(2\times 2)$

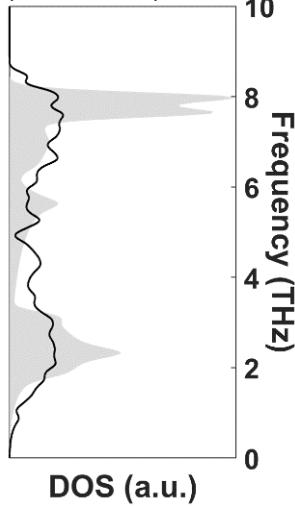


Surface vibration of GaAs(111)B

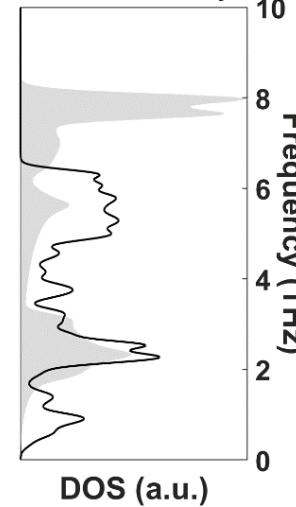
(111)B As trimer-100(2×2)



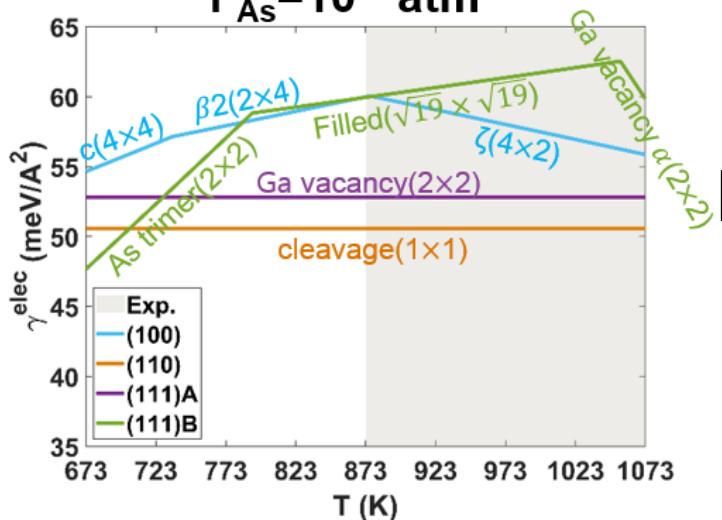
(111)B Filled($\sqrt{19} \times \sqrt{19}$)



(111)B Ga vacancy α (2×2)



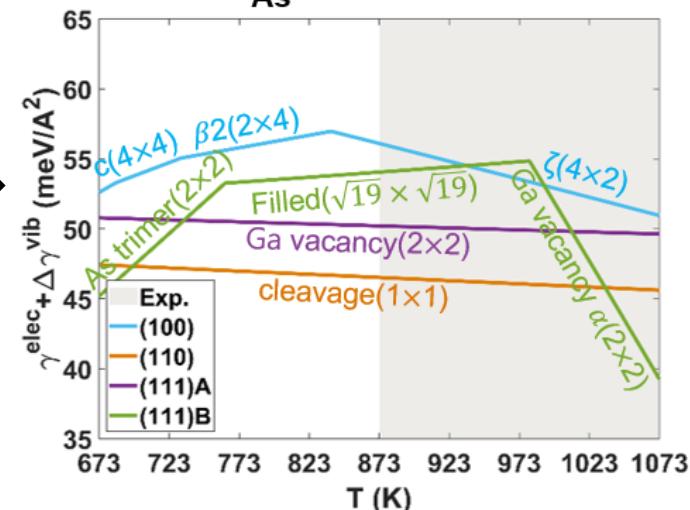
$P_{\text{As}} = 10^{-5} \text{ atm}$



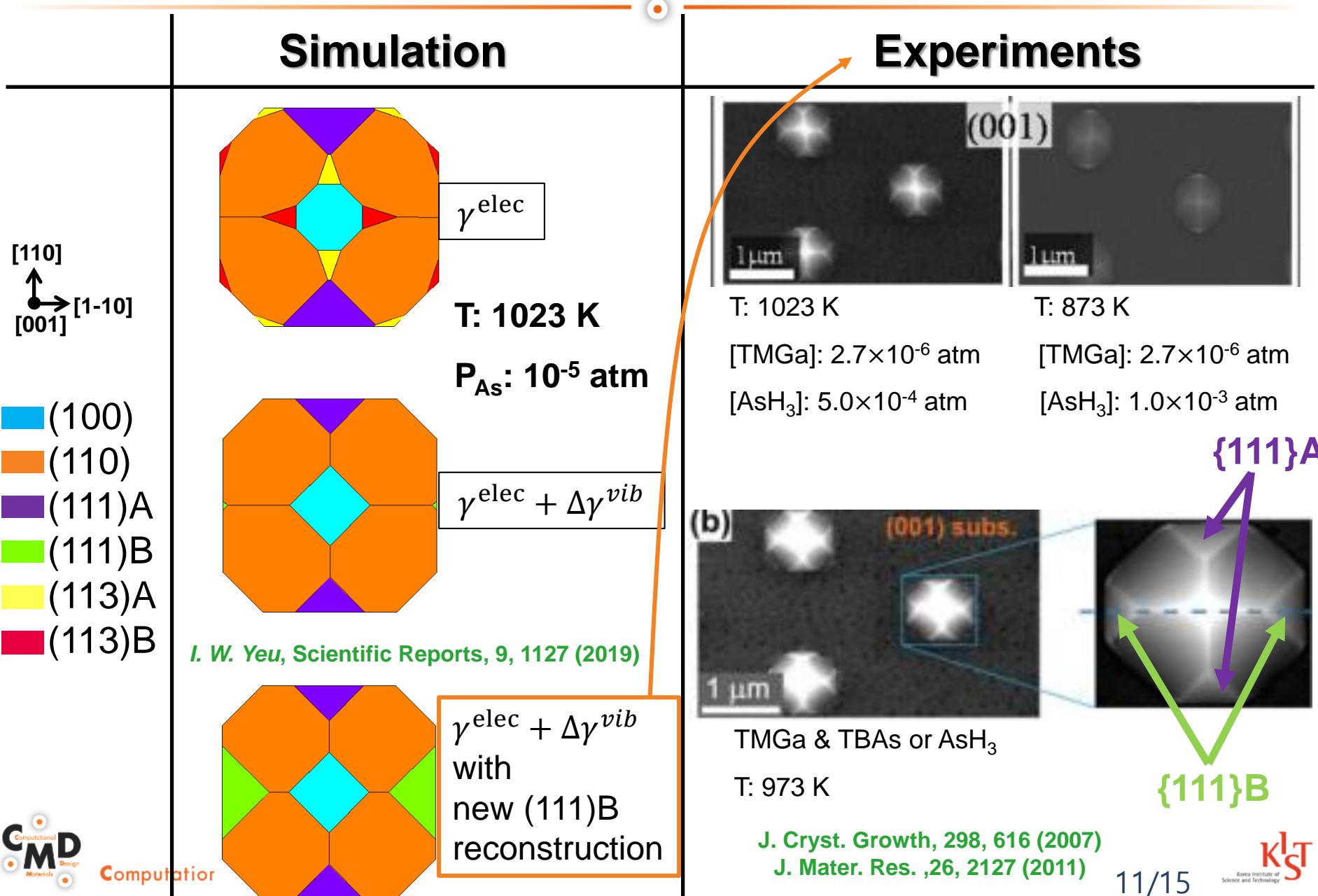
Surface vib.

$$\gamma = \gamma^{\text{elec}} + \Delta\gamma^{\text{vib}}$$

$P_{\text{As}} = 10^{-5} \text{ atm}$



Wulff shape vs. homo-epitaxial shape



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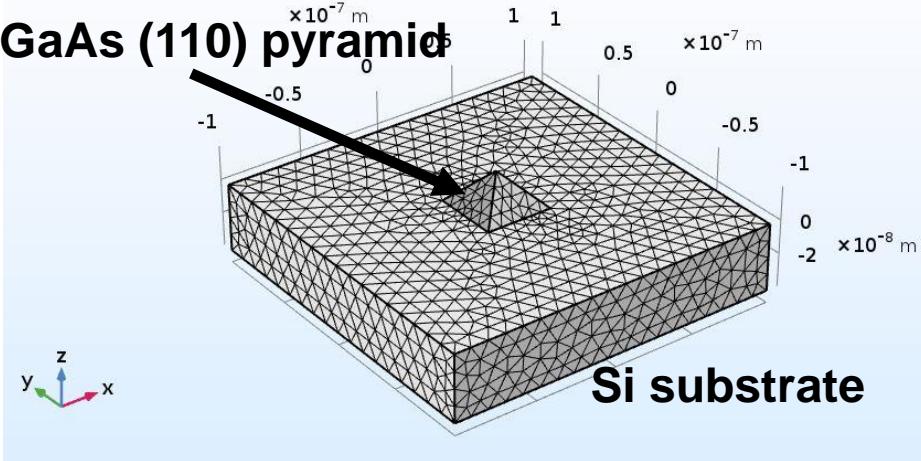
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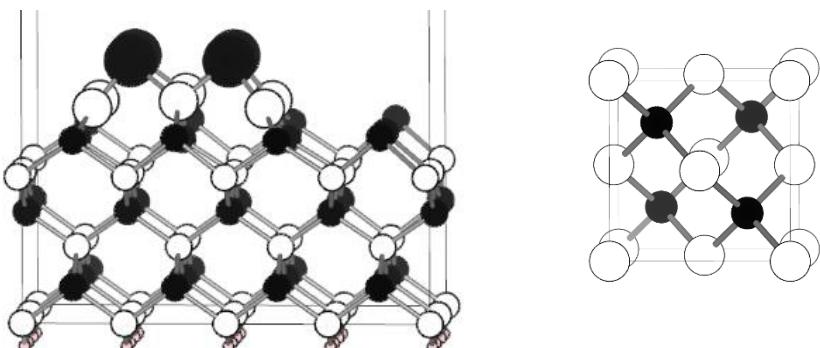
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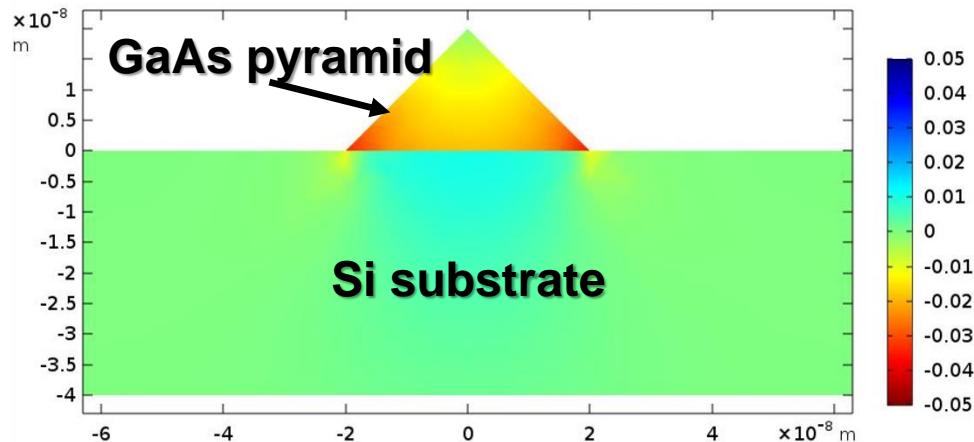
Strained shape: FEM +DFT



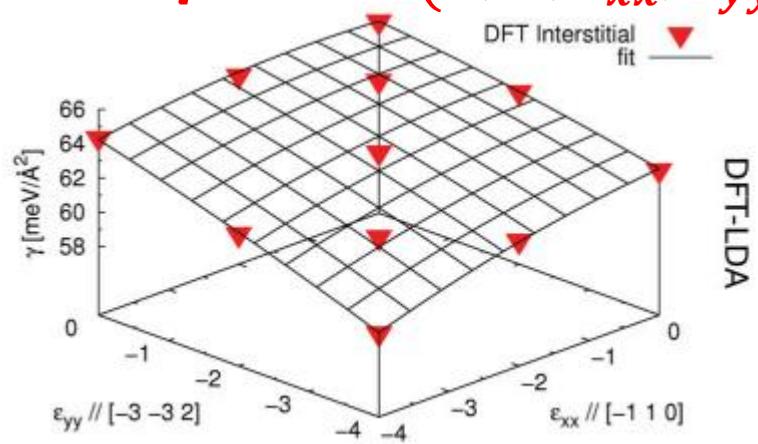
$$\gamma^{strained} = E_{surf}^{strained} - E_{bulk}^{strained}$$



FEM: Strain distribution ($\epsilon_{xx}, \epsilon_{yy}$)



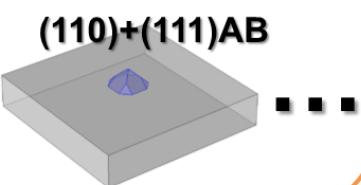
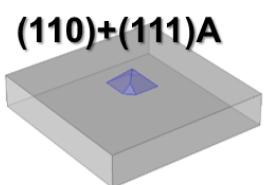
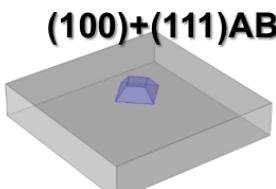
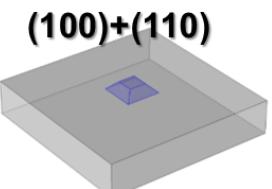
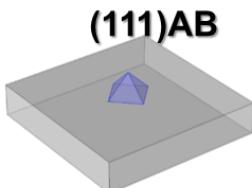
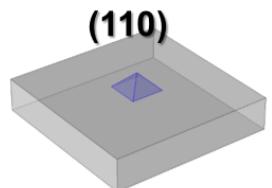
DFT: $\gamma^{strained}(T, P, \epsilon_{xx}, \epsilon_{yy})$



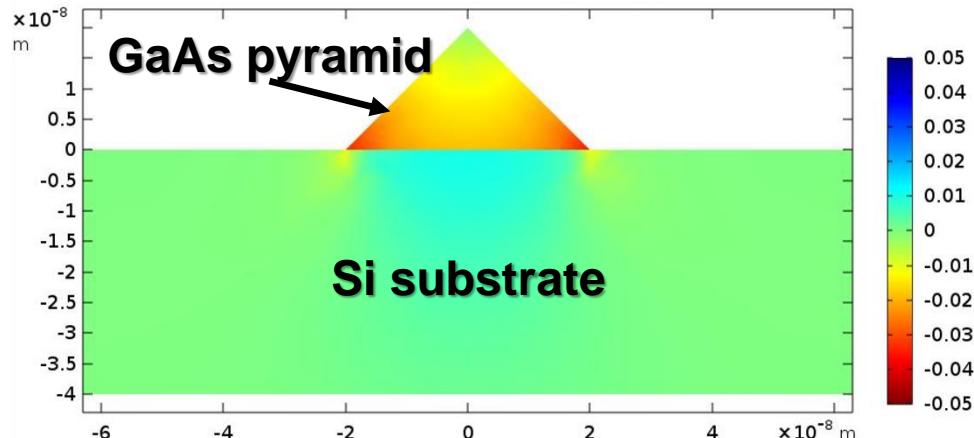
$$\gamma(\epsilon_{xx}, \epsilon_{yy}) = \gamma_0 + \sigma_{xx}\epsilon_{xx} + \sigma_{yy}\epsilon_{yy} + S_{xx}\epsilon_{xx}^2 + S_{yy}\epsilon_{yy}^2 + S_{xy}\epsilon_{xx}\epsilon_{yy}$$

Strained shape: FEM +DFT

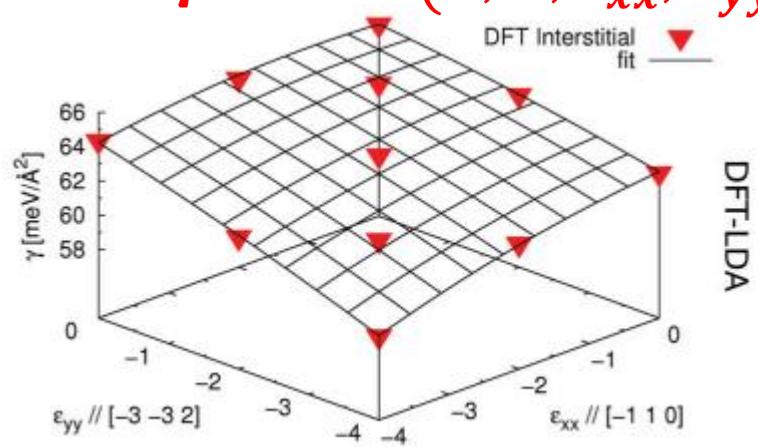
Various Faceted Forms



FEM: Strain distribution($\epsilon_{xx}, \epsilon_{yy}$)



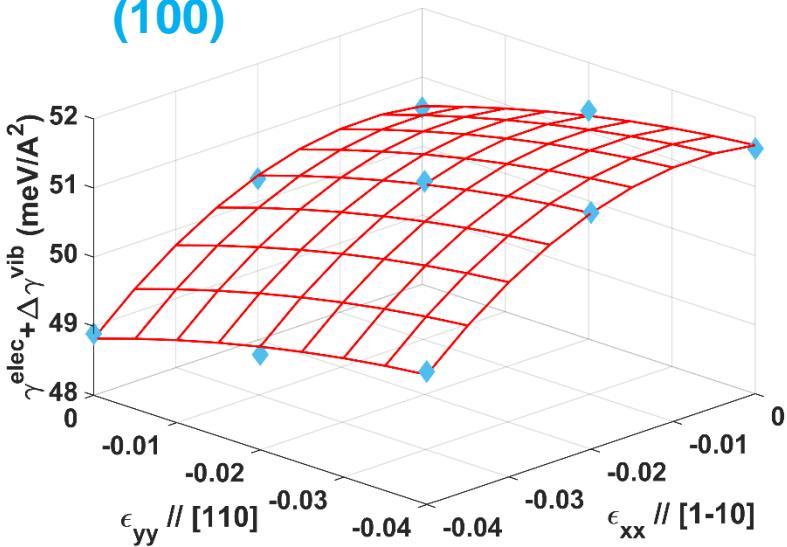
DFT: $\gamma^{\text{strained}}(T, P, \epsilon_{xx}, \epsilon_{yy})$



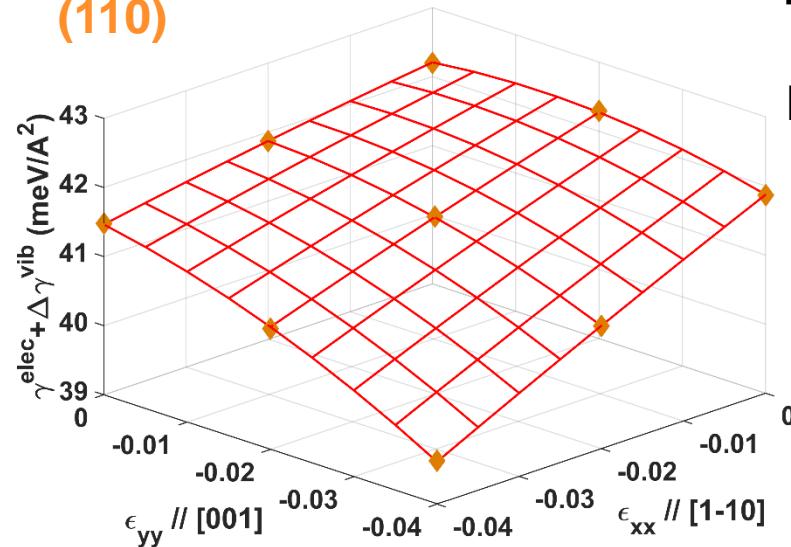
$$\gamma(\epsilon_{xx}, \epsilon_{yy}) = \gamma_0 + \sigma_{xx}\epsilon_{xx} + \sigma_{yy}\epsilon_{yy} + S_{xx}\epsilon_{xx}^2 + S_{yy}\epsilon_{yy}^2 + S_{xy}\epsilon_{xx}\epsilon_{yy}$$

Strained surface energy

(100)



(110)



T: 1023 K

P_{As}: 10⁻⁵ atm

(100) DFT

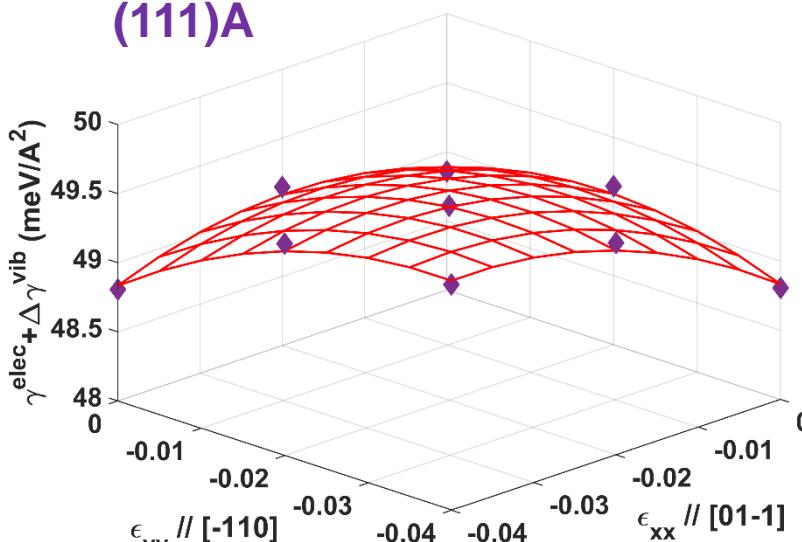
(110) DFT

(111)A DFT

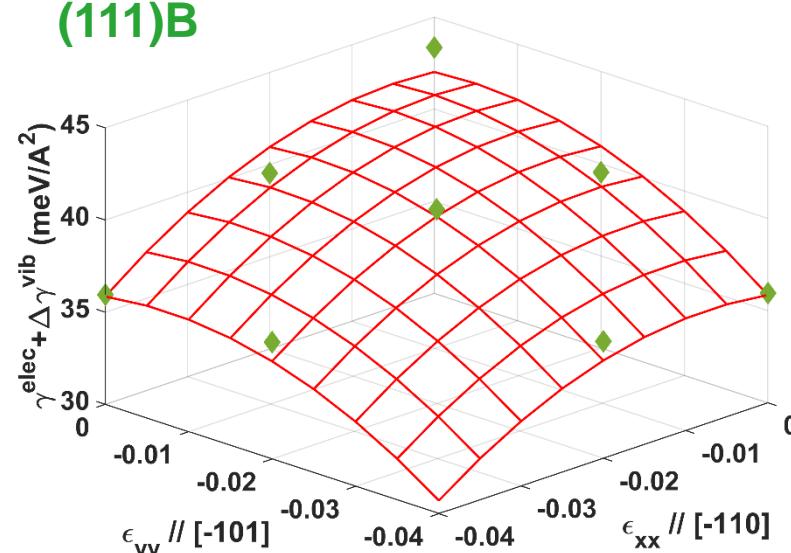
(111)B DFT

Fit

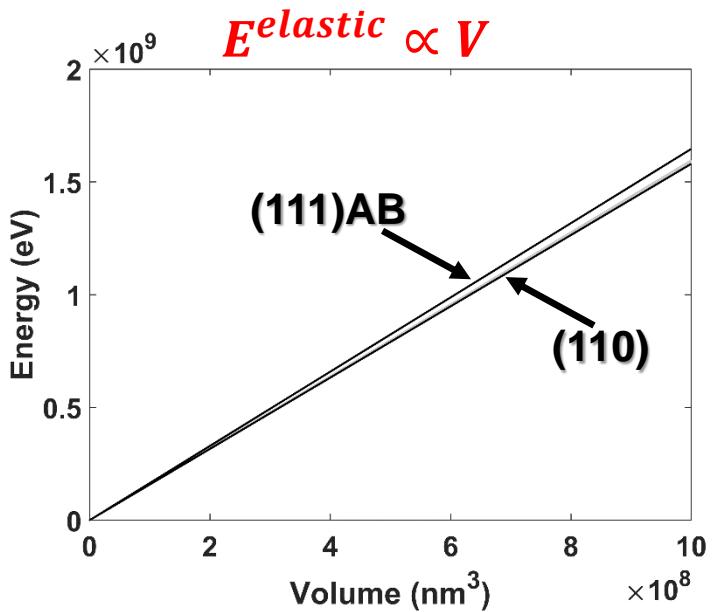
(111)A



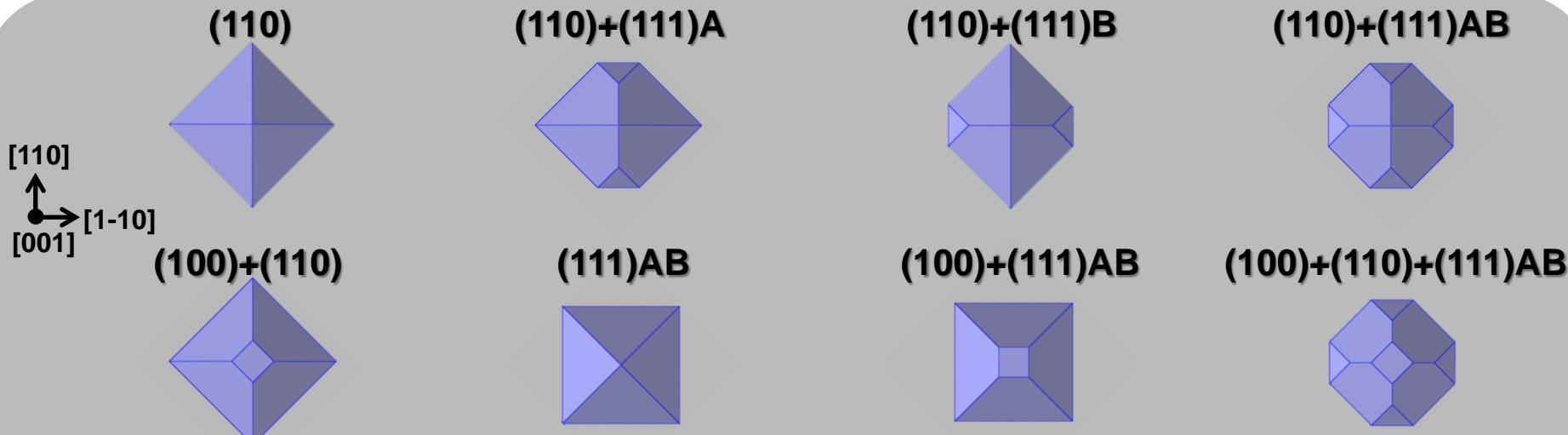
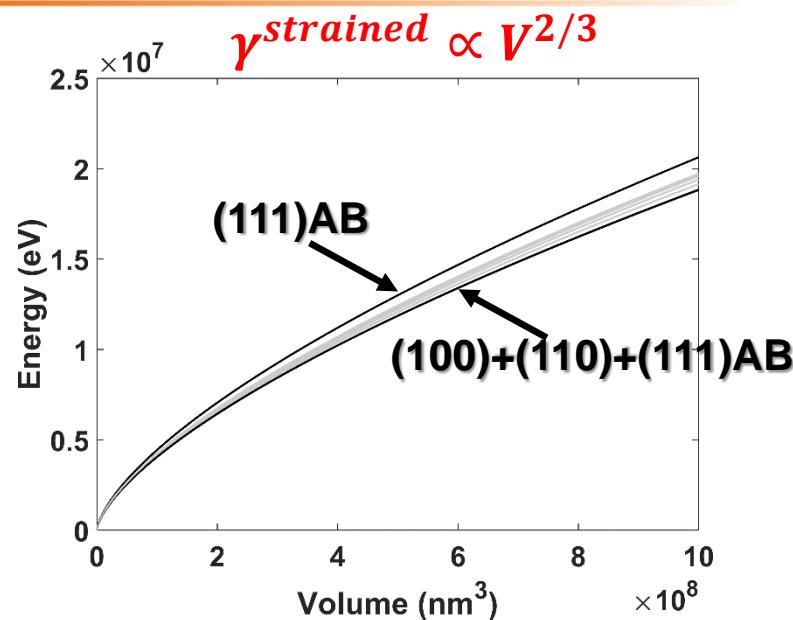
(111)B



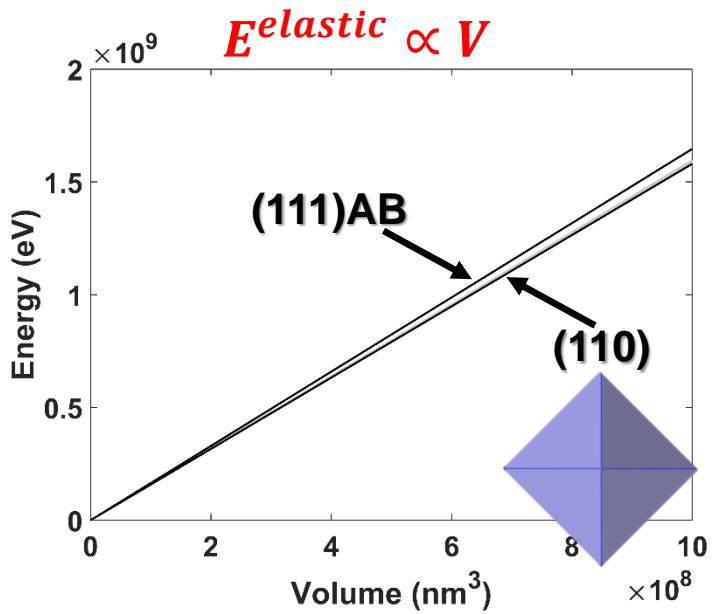
Energy(T, P, V) of strained crystal



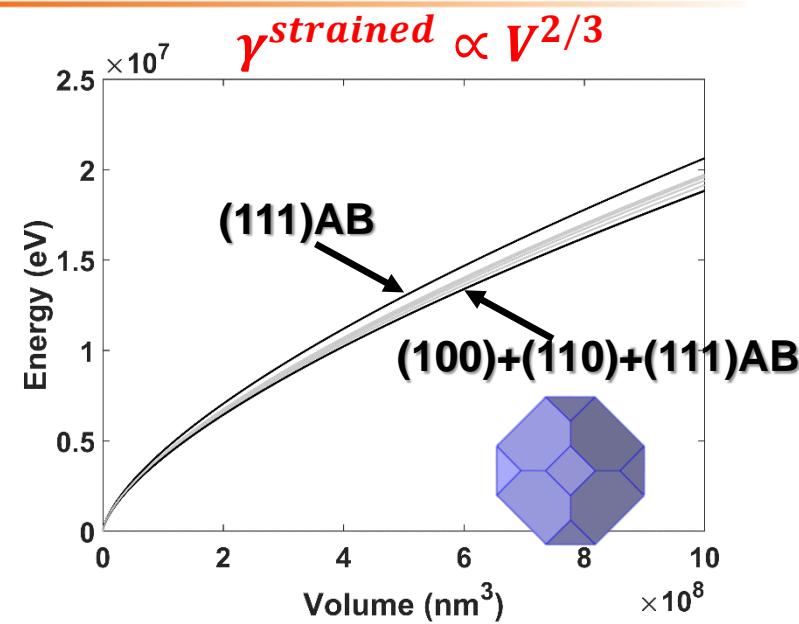
$T: 1023 \text{ K}$
 $P_{\text{As}}: 10^{-5} \text{ atm}$



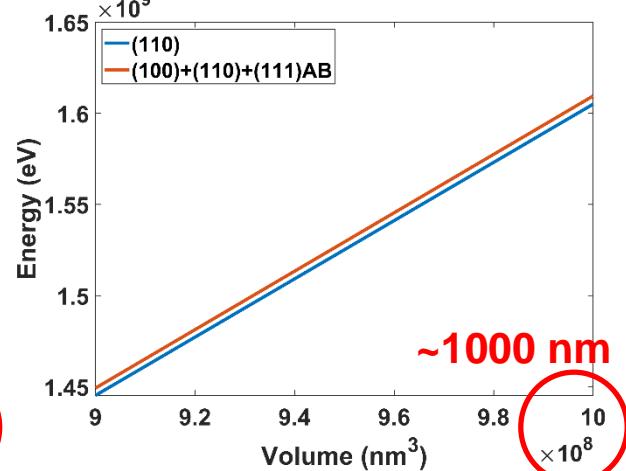
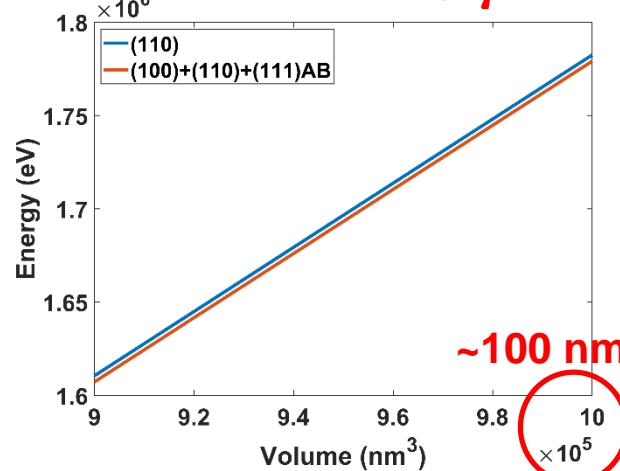
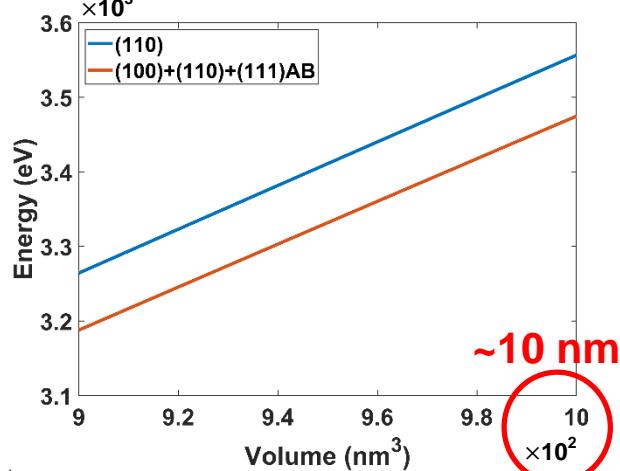
Energy(T, P, V) of strained crystal



T: 1023 K
 $P_{\text{As}}: 10^{-5} \text{ atm}$



$$E^{\text{total}} = E^{\text{elastic}} + \gamma^{\text{strained}}$$



Unstrained shape vs. Strained shape

